

Refine Search

Search Results -

Terms	Documents
L5 and (CMP or chemical mechanical)	1

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Search:

L6

Refine Search

Recall Text

Clear

Interrupt

Search History

DATE: Wednesday, May 25, 2005 [Printable Copy](#) [Create Case](#)

<u>Set</u> <u>Name</u> side by side	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L6</u>	L5 and (CMP or chemical mechanical)	1	<u>L6</u>
<u>L5</u>	6815705.pn.	2	<u>L5</u>
<u>L4</u>	L3 and ((CMP or chemical mechanical) same (opening or via or trench))	70	<u>L4</u>
<u>L3</u>	L2 and electrode and tungsten and oxide	158	<u>L3</u>
<u>L2</u>	L1 and (CMP or chemical mechanical)	305	<u>L2</u>
<u>L1</u>	memory same (phase change)	3214	<u>L1</u>

END OF SEARCH HISTORY

Refine Search

Your wildcard search against 10000 terms has yielded the results below.

Your result set for the last L# is incomplete.

The probable cause is use of unlimited truncation. Revise your search strategy to use limited truncation.

Search Results -

Terms	Documents
L4 and ((CMP or chemical mechanical) near6 third near10 (insulat\$ or dielectric))	4

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DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ			
<u>L5</u>	L4 and ((CMP or chemical mechanical) near6 third near10 (insulat\$ or dielectric))	4	<u>L5</u>
<u>L4</u>	L3 and electrode and tungsten and oxide	43	<u>L4</u>
<u>L3</u>	L2 and 438/\$.ccls.	91	<u>L3</u>
<u>L2</u>	L1 and chemical mechanical polish\$	201	<u>L2</u>
<u>L1</u>	memory same (phase change)	3214	<u>L1</u>

END OF SEARCH HISTORY